

ILLUMINATION SYSTEM WITH A PLURALITY OF LIGHT SOURCES

Abstract

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The invention concerns an illumination system for wavelengths ≤ 193 nm, especially for EUV-lithography with

a plurality of light sources

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a mirror device for creating secondary light sources comprising several mirrors, said mirrors are comprising raster elements.

The invention is characterized in that

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the plurality of light sources are coupled together in order to illuminate the exit pupil of the illumination system up to a predetermined degree of filling.